Cont A3

is provided with a means for impressing direct current or alternating current power.

Please add the following:

- 8. The semiconductor manufacturing apparatus according to Claim 2, wherein said vacuum vessel can be divided into a part including said processing chamber and a part having said substrate transport mechanism.
- 9. The semiconductor manufacturing apparatus according to Claim 2 comprising a plasma generation mechanism for generating plasma in said processing chamber.
- 10. The semiconductor manufacturing apparatus according to Claim 3 comprising a plasma generation mechanism for generating plasma in said processing chamber.
- 11. The semiconductor manufacturing apparatus according to Claim 10, wherein said plasma generation mechanism radiates microwave thorough a slot antenna.

IN THE ABSTRACT

Please delete the abstract on file and replace it with the attached ABSTRACT OF THE DISCLOSURE.

Respectfully submitted,

Randall J. Knuth

Registration No. 34,644

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RJK/jrc

Encs: ABSTRACT OF THE DISCLOSURE

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